

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2	"2003197590".pn.	FPRS; EPO; JPO; DERWENT	OR	ON	2010/05/08 01:15
L2	64	(hydrophobic and hydrophilic) and (substrate wafer semiconductor workpiece) and (rins\$3 wash\$3 clean\$3) and (water near\$3 (pure\$2 purif\$3 purification demin demineraliz\$5))	FPRS; EPO; JPO; DERWENT	OR	ON	2010/05/08 01:22
L3	22	2 and (surface area region) and ("both" mixed)	FPRS; EPO; JPO; DERWENT	OR	ON	2010/05/08 01:24
L4	61	2 and (surface area region)	FPRS; EPO; JPO; DERWENT	OR	ON	2010/05/08 01:24
S1	1	"20070131256".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 14:52
S2	2	("20080173333" "5997653").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 14:53
S3	1	S1 and (hydrophobic hydrophilic)	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:24
S4	2	S2 and (hydrophobic hydrophilic)	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:24
S5	1	"20030084925".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:26
S6	0	S2 and S5	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:26
S7	3	S2 S5	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:26
S8	3	S7 and (hydrophobic hydrophilic)	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 15:26

S9	1006	((hydrophobic and hydrophilic) same (substrate wafer semiconductor workpiece)) and ((rins \$3 wash\$3 clean\$3) same (water near3 (pure\$2 purif\$3 purification demin demineraliz\$5)))	US-PGPUB; USPAT	OR	ON	2010/05/07 15:34
S10	728	S9 and water same film	US-PGPUB; USPAT	OR	ON	2010/05/07 15:36
S11	564	S10 and water same (reduc\$3 less lessen\$3 small\$2)	US-PGPUB; USPAT	OR	ON	2010/05/07 15:37
S12	141	S11 and water same (reduc\$3 less lessen\$3 small\$2) same (mov\$3 rotat\$3)	US-PGPUB; USPAT	OR	ON	2010/05/07 15:38
S13	114	S12 and water same (suppl\$4 feed\$3 using use\$1) same (reduc\$3 less lessen\$3 small\$2) same (mov\$3 rotat\$3)	US-PGPUB; USPAT	OR	ON	2010/05/07 15:39
S14	29	S13 and water same (suppl\$4 feed\$3 using use\$1) same (reduc\$3 less lessen\$3 small\$2) same (mov\$3 rotat\$3) same film	US-PGPUB; USPAT	OR	ON	2010/05/07 15:39
S15	1	"20030084925".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 17:39
S16	1	S15 and (hydrophobic hydrophilic)	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 17:39
S17	1006	((hydrophobic and hydrophilic) same (substrate wafer semiconductor workpiece)) and ((rins \$3 wash\$3 clean\$3) same (water near3 (pure\$2 purif\$3 purification demin demineraliz\$5)))	US-PGPUB; USPAT	OR	ON	2010/05/07 17:41
S18	182	S17 and (surface area) same ("both") same (hydrophobic and hydrophilic)	US-PGPUB; USPAT	OR	ON	2010/05/07 17:41

S19	21	S18 and (surface area near5 ("both" near5 (hydrophobic and hydrophilic)	US-PGPUB; USPAT	OR	ON	2010/05/07 17:42
S20	6	("5882433" "6221168" "6398975" "6406551" "6491764").PN. OR ("7011715").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 17:48
S21	4	S20 and (hydrophobic and hydrophilic)	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 17:48
S22	189	S17 and (surface area region) same ("both") same (hydrophobic and hydrophilic)	US-PGPUB; USPAT	OR	ON	2010/05/07 17:50
S23	397	((substrate wafer semiconductor workpiece) near5 (rins \$3 wash\$3 clean\$3)) and ((surface area region) near5 ("both" mixed) near5 (hydrophobic and hydrophilic))	US-PGPUB; USPAT	OR	ON	2010/05/07 17:52
S24	90	S23 and ((substrate wafer semiconductor workpiece) near5 (rins \$3 wash\$3 clean\$3) near5 water)	US-PGPUB; USPAT	OR	ON	2010/05/07 17:53
S25	1	"6058945".pn.	US-PGPUB; USPAT; USOCR	OR	ON	2010/05/07 22:51

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